

ON-CHIP INDUCTOR HAVING IMPROVED QUALITY FACTOR AND METHOD
OF MANUFACTURE THEREOF

ABSTRACT OF THE DISCLOSURE

5

An on-chip inductor may be fabricated by creating at least one dielectric layer, creating at least one conductive winding on the at least one dielectric layer and creating: (1) a P-well layer having a major surface
10 parallel to a major surface of the dielectric layer, (2) field oxide layer having a major surface parallel to a major surface of the dielectric layer, (3) P-well and field oxide layer, or (4) a poly-silicon layer having a major
15 surface parallel to a major surface of the dielectric layer.